

NCCA VS
CMP USER GROUP
(<https://nccavs-usergroups.avs.org/>)

Topic: Advancements in CMP Applications and Research

Meeting Date: December 1, 2022

Time: 1:00 pm – 4:30 pm (Central Time Zone)

Location: Virtual Meeting

Co-Chairs:

Scott Lawing, Kinik North America, slawing@kinikna.com

Tricia Burroughs, Global Foundries, tricia.burroughs@globalfoundries.com

AGENDA:

1:00 pm Welcome and Acknowledgment of sponsors; by conference co-chairs Scott Lawing (**Kinik North America**) and Tricia Burroughs (**GlobalFoundries**)

1:10 pm Semiconductors and the CHIPS act: What Happens Next?, Dr. Eric Breckenfeld, (**Semiconductor Industry Association**)

1:35 pm Economic Trends Shaping Semiconductor Demand, Duncan Meldrum. PhD, CBE (**Hilltop Economics LLC**)

2:00 pm Trends with Sustainability and Emerging Developments in Wet and Dry Processes, Michael Corbett (**Linx Consulting**)

2:35 pm CMP Removal Rate Modeling with the Shear Force Law, Len Borucki, Y. Sampurno and A. Philipossian (**Araca, Inc.**)

3:00 pm Quantitative Analysis of CMP Slurry Additives Using Raman Spectroscopy, Timothy Holt and Michelle Sestak (**HORIBA Instruments Inc.**)

3:25 pm Slurry Activation Through Flucto-CMP, A. Philipossian and Yasa Sampurno (**Araca, Inc**) Fritz Redeker, Kiana Cahue and Jason Keleher (**Lewis University**)

3:50 pm Advanced CMP Cleaning Solutions, Geoffrey Yuxin Hu (**Brizon Inc.**)